



Semiconductor  
Research  
Corporation

# SUPREME – a JUMP2.0 center Overview

April 26, 2023

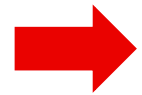
SAB-Director F2F Meeting, @ADI  
Huili Grace Xing, Cornell University  
Tomas Palacios, MIT



# Overview

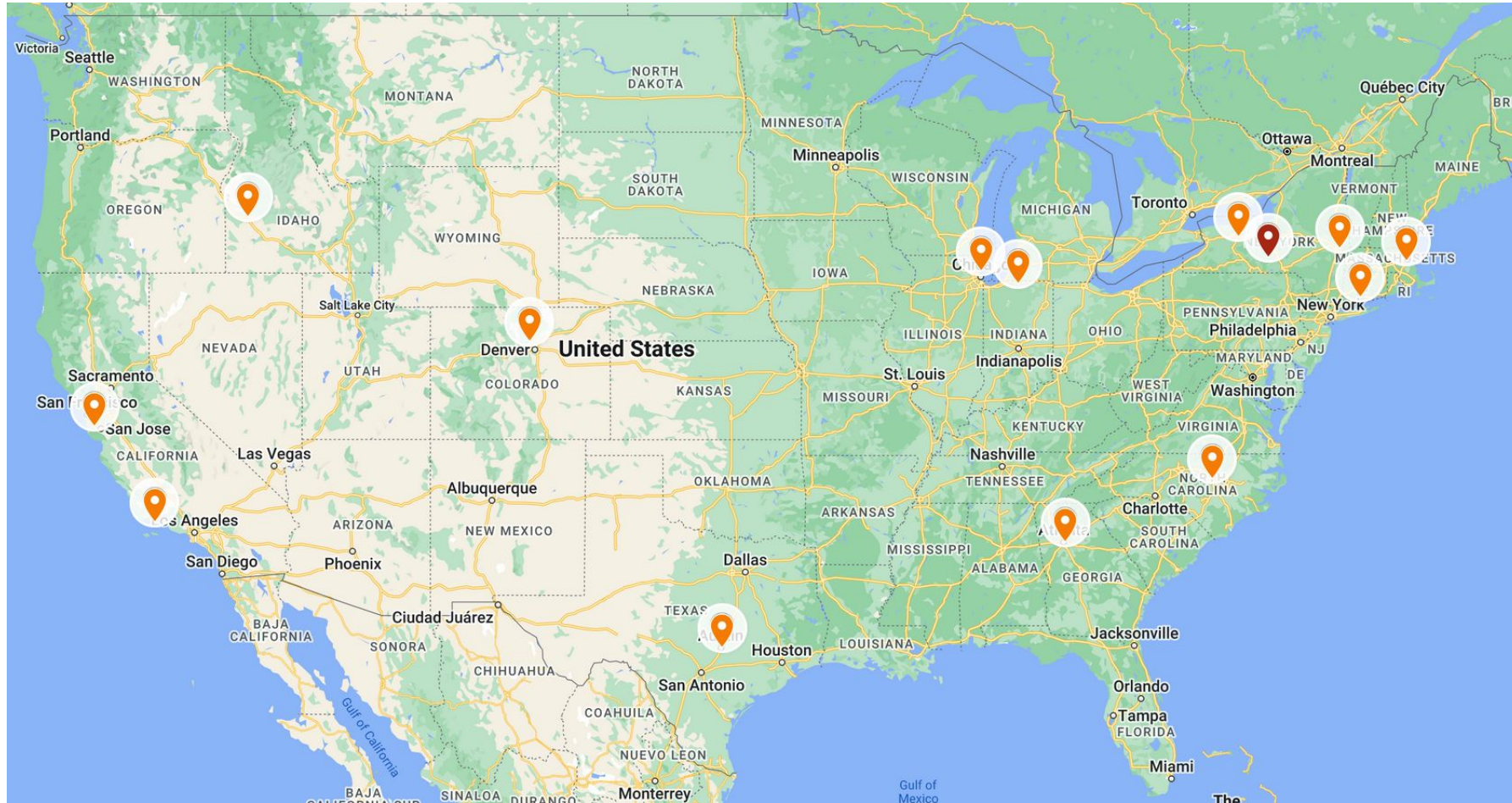
- SUPREME Team overview
- Thrusts
- Q&A (~45 min)

# JUMP 2.0, Tentative Annual Review Dates



Center	Tentative Dates	Tentative Location
COCOSYS	May 16-17, 2023	Atlanta, Georgia Tech
CUBIC	June 27-28, 2023	NYC, Columbia
SUPREME	August 2-3, 2023	Ithaca, Cornell University
CHIMES	September 5-6, 2023	State College, Penn State
ACE	October 4-5, 2023	Urbana, UIUC
COGNISENSE	October 11-12, 2023	Atlanta, Georgia Tech
PRISM	October 8-9, 2023	La Jolla, UCSD

# 14 Universities – 1 Center



# 25 PIs – One SUPREME



# PIs



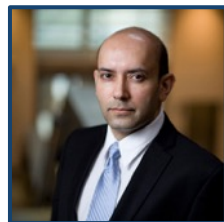
Grace Xing



Tomas Palacios



Elton  
Graugnard



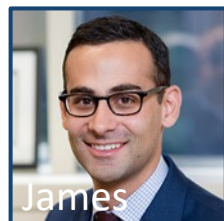
Farhan Rana



Cornell University



Chris  
van de Walle



James  
Rondinelli



Mike Niemier



James Hwang



Debdeep Jena



Dan Ralph



Judy Cha



Rensselaer



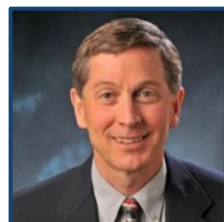
Georgia  
Tech.



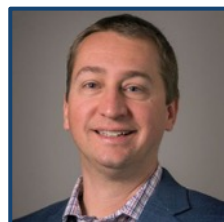
BOISE STATE UNIVERSITY



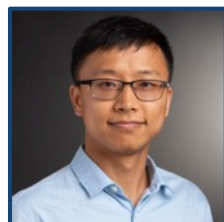
Eric Pop



Steve George



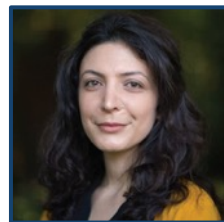
Chris Hinkle



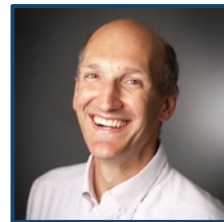
Kai Ni



Daniel Gall



Farnaz Niroui



Darrell Schlom

Yale



TEXAS  
The University of Texas at Austin



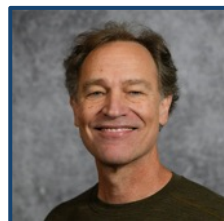
Northwestern  
University



Feliciano  
Giustino



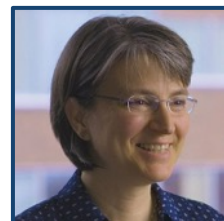
Asif Khan



Greg Parsons



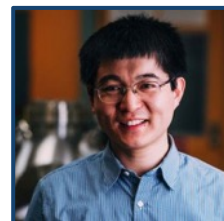
Hong Tang



Bilge Yildiz



Jing Kong



Luqiao Liu



RIT



Stanford  
University

UCSB



SRC

SUPREME  
SUPERior Energy-efficient Materials and dEvices

# Organization Chart

**Center 7: SUPeRior Energy-efficient Materials and dEVICES (SUPREME)**



**H. Grace Xing<sup>v</sup>**  
Director

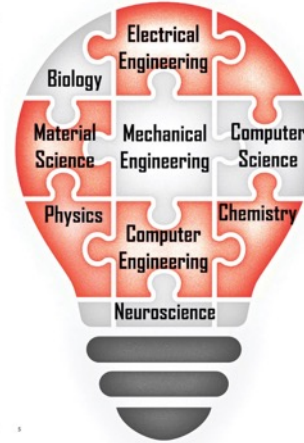


**Tomas Palacios**  
Associate Director



**Thomas Dienel**  
Managing Director

**FUNCTIONS**  
Project, Budget & Conflict Management, Strategic Planning, Annual Meeting Coordination, IP/Spin-off Coordination, Research Development, Reporting




**Scientific Advisory Board**  
Visionaries funding a shared technology future



**FUNCTIONS**  
Center Evaluation, Strategic Planning and PI Re-alignment, IP Filing Decision, Center to Center Collaboration


**Thrust 1: Digital & Analog**



**Debdeep Jena** Thrust Lead

- Tomas Palacios (Co-Lead)
- H. Grace Xing
- James Hwang<sup>1</sup>
- Farnaz Niroui<sup>^1v</sup>
- Luqiao Liu<sup>\*^</sup>

**Thrust 2: Memories & Applications**



**Asif Khan<sup>^</sup>** Thrust Lead

- Dan Ralph (Co-Lead)
- Kai Ni<sup>^</sup>
- Mike Niemier\* (Liaison Lead)
- Bilge Yildiz<sup>1v</sup>

**Thrust 3: Interconnects & Metrology**



**Farhan Rana** Thrust Lead

- Daniel Gall (Co-Lead)
- Hong Tang<sup>1</sup>
- Judy Cha<sup>\*^v</sup>
- Chris Hinkle
- Eric Pop

**Thrust 4: Materials Discovery & Processing**

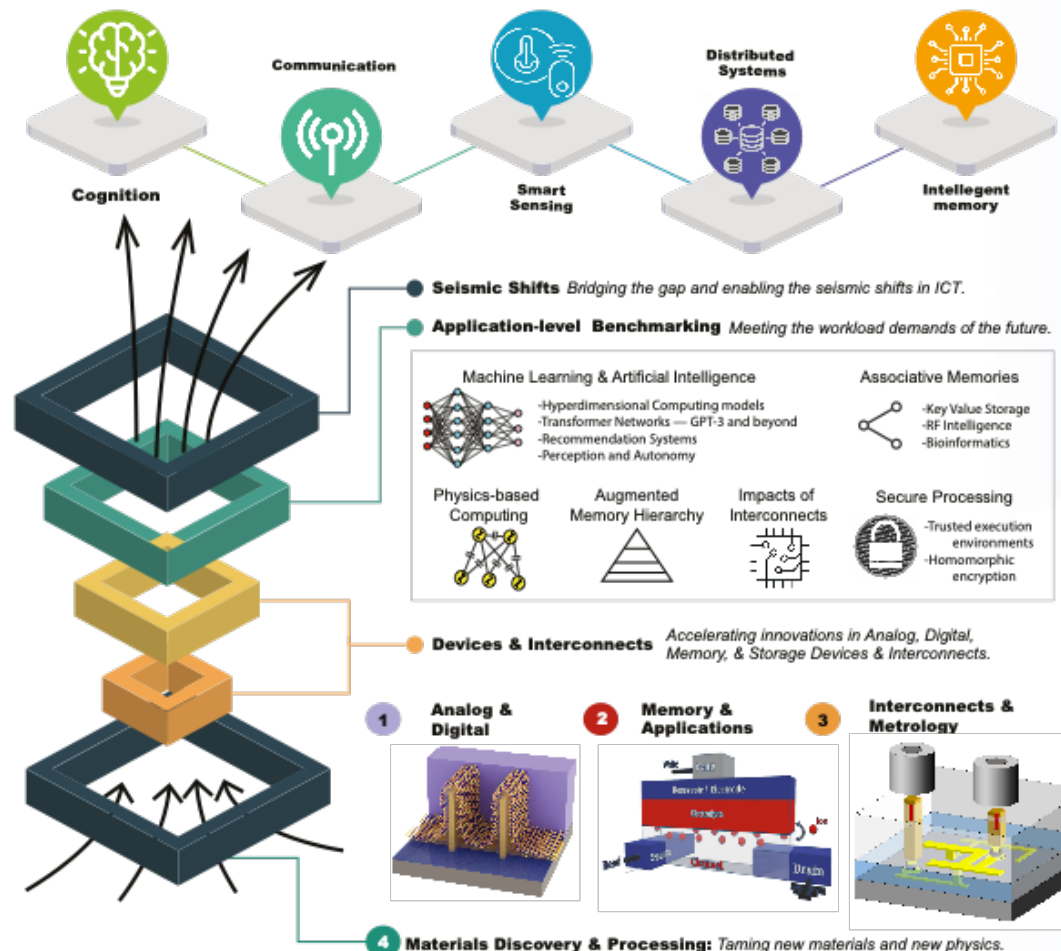


**Feliciano Giustino<sup>o</sup>**  
Thrust Lead

- Jing Kong<sup>1v</sup> (Co-Lead)
- Steven George
- Chris Van de Walle
- Darrell Schlom\*
- James Rondinelli
- Elton Graugnard
- Greg Parsons

\* Liaisons to interface with other JUMP 2.0 centers  
<sup>1</sup> First-time SRC Performers (6)  
<sup>v</sup> Female Faculty (5)  
<sup>^</sup> Young Faculty (5)

**Note: Only primary thrust affiliation is shown.**



● **Seismic Shifts** Bridging the gap and enabling the seismic shifts in ICT.

● **Application-level Benchmarking** Meeting the workload demands of the future.

<b>Machine Learning &amp; Artificial Intelligence</b> <ul style="list-style-type: none"> <li>-Hyperdimensional Computing models</li> <li>-Transformer Networks — GPT-3 and beyond</li> <li>-Recommendation Systems</li> <li>-Perception and Autonomy</li> </ul>	<b>Associative Memories</b> <ul style="list-style-type: none"> <li>-Key Value Storage</li> <li>-RF Intelligence</li> <li>-Bioinformatics</li> </ul>
<b>Physics-based Computing</b> <ul style="list-style-type: none"> <li>-Augmented Memory Hierarchy</li> <li>-Impacts of Interconnects</li> </ul>	<b>Secure Processing</b> <ul style="list-style-type: none"> <li>-Trusted execution environments</li> <li>-Homomorphic encryption</li> </ul>

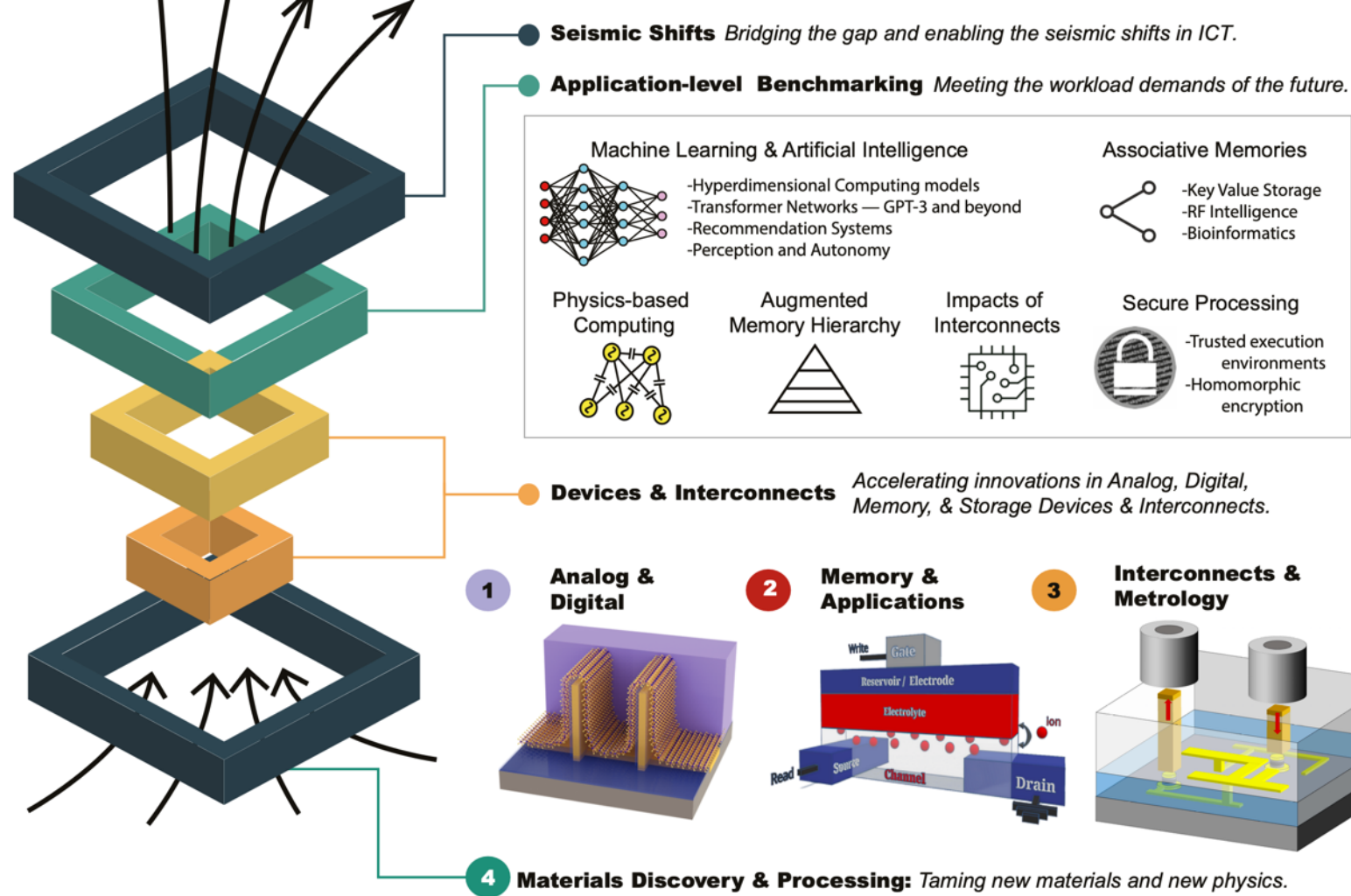
● **Devices & Interconnects** Accelerating innovations in Analog, Digital, Memory, & Storage Devices & Interconnects.

<b>1 Analog &amp; Digital</b> 	<b>2 Memory &amp; Applications</b> 	<b>3 Interconnects &amp; Metrology</b> 
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● **4 Materials Discovery & Processing:** Taming new materials and new physics.

Accelerated Materials Discovery	AI-assisted Synthesis & Manufacturing	Processing & Metrology
 TMDs $MoSe_2, WS_2, WSe_2$	 Nitrides $AlScN, ScGaN, BN, InN$	 Oxide interconnect metals $PdCoO_2, PdRhO_2$
Conventional semiconductors $Si, SiGe, Ge, GaN, SiC$	2-D Materials $InN, ZnO, SnSe$	Intermetallic interconnect metals $VPt_2, MoNi_2, NiIr_3$
Anisotropic spin sources $PtO, Sr_3Ru_2O_7$	Proton reservoir in ECRAM - Metal hydrides, $PdH_x$	Weyl semi-metals, Heusler alloys - $Co_2MnGa, Mn_3Sn$
	Proton electrolyte in electrochemical RAM (ECRAM) - $HfO_2, ZrO_2$	
	Synthetic antiferromagnets $FeCoB/Pt/Ru/Pt/FeCoB$	
	Proton channel in ECRAM - $MoO_3$	
	Conductive boride-based interconnect metals - $YCo_3B_4, NbFeB, Mn_2B$	
	p-channel oxides $Ta_2SnO_6, Ba_2BiTaO_6$	





**Accelerated Materials Discovery**

**AI-assisted Synthesis & Manufacturing**

**Processing & Metrology**



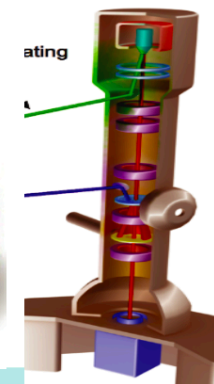
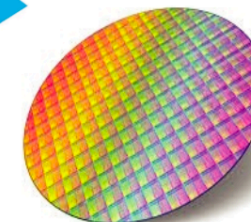
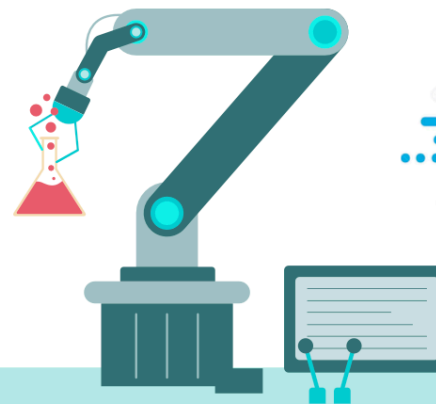
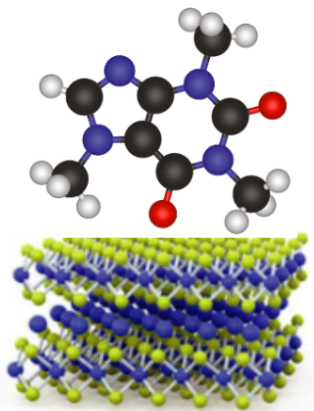
4

**Materials Discovery & Processing:** *Taming new materials and new physics.*

**Accelerated Materials Discovery**

**AI-assisted Synthesis & Manufacturing**

**Processing & Metrology**



TMDs  
MoSe<sub>2</sub>, WS<sub>2</sub>, WSe<sub>2</sub>

Nitrides  
AlScN, ScGaN, BN, InN

Proton electrolyte in electrochemical  
RAM (ECRAM) - HfO<sub>2</sub>, ZrO<sub>2</sub>

Synthetic antiferromagnets  
FeCoB/Pt/Ru/Pt/FeCoB

Oxide interconnect metals  
PdCoO<sub>2</sub>, PdRhO<sub>2</sub>

Conventional semiconductors  
Si, SiGe, Ge, GaN, SiC

2-D Materials  
InN, ZnO, SnSe

Ferroelectrics  
SnS, AlScN, BaTiO<sub>3</sub>

Proton channel in  
ECRAM - MoO<sub>3</sub>

Intermetallic interconnect metals  
VPt<sub>2</sub>, MoNi<sub>2</sub>, NiIr<sub>3</sub>

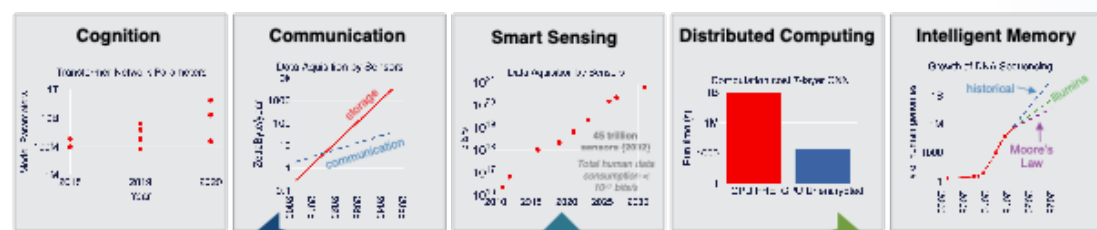
Anisotropic spin sources  
PtO, Sr<sub>3</sub>Ru<sub>2</sub>O<sub>7</sub>

Proton reservoir in  
ECRAM - Metal hydrides, PdH<sub>x</sub>

Conductive boride-based interconnect  
metals - YCo<sub>3</sub>B<sub>2</sub>, NbFeB, Mn<sub>2</sub>B

p-channel oxides  
Ta<sub>2</sub>SnO<sub>6</sub>, Ba<sub>2</sub>BiTaO<sub>6</sub>

Weyl semi-metals, Heusler  
alloys - Co<sub>2</sub>MnGa, Mn<sub>3</sub>Sn



**Roadmapping to ensure system-level impact**

**Digital logic, control**  
 • 0.3 fJ/switch

**Next gen analog & mixed signal**  
 • > 10dB increase in SNR for same P<sub>oc</sub>  
 • I<sub>on</sub> = 5 mA/μm, SS=20 mV/decade  
 • RF amplifiers with 10x better performance

**High frequency, THz**  
 • 1W at 300 GHz with 30% PAE

**Beyond CMOS**  
 • < 5ns switching + 10000X < energy  
 • GHz spin torque oscillators  
 • ΔR > 500Q after magnet reversal

**Benchmarking against target device metrics**

**Materials-driven digital/analog revolution**

**Roadmapping to ensure system-level impact**

**Energy for HD search**

**100000X energy savings, iso-accuracy with GPU for AI workloads**

Metric	2T-1MTJ	FeFET	2T eDRAM
Destructive Read?	No	No	No
Program voltage	< 0.5 V	1.8V	1V
Write energy	10-50 fJ	< 1 fJ	< 1 fJ
Write delay	< 1 ns	< 10 ns	1-10 ns
Read speed	< 1 ns	< 1 ns	< 1 ns
Endurance	> 10 <sup>15</sup>	> 10 <sup>12</sup>	> 10 <sup>12</sup>

**Benchmarking against target device metrics**

**Materials-driven memory/storage revolution**

**Roadmapping to ensure system-level impact**

**>10X reduction in interconnect latency**

**Electrical interconnects**  
 • >9X lower line resistance at 8 nm 1/2-pitch  
 • >80% specular surface scattering

**Inter-chip optical interconnects**  
 • ≤ .01 μm laser size, ≥ 160 GHz direct mod speed  
 • ≤ 2 ps laser turn on time

**Benchmarking against target device metrics**

**Materials-driven interconnect revolution**

TMDs ■ Oxides ■ Ferroelectric Nitrides, SnSe, BaTiO<sub>3</sub> ■ P-channel materials: Ta<sub>2</sub>SnO<sub>5</sub>, Ba<sub>2</sub>BiTaO<sub>9</sub> ■ Non-cubic metals PtO, Sr<sub>2</sub>Ru<sub>2</sub>O<sub>7</sub> ■ Nitrides ■ Hydrogen reservoir PdH<sub>2</sub> ■ Heusler Alloys, Weyl semi-metals Co<sub>2</sub>MnGa, Mn<sub>3</sub>Sn ■ H<sup>+</sup> conducting layer: MoO<sub>3</sub> ■ Synthetic antiferromagnets: FeCoB/Pt/Ru/Pt/FeCoB ■ Conductive delafossite oxides: PdCoO<sub>2</sub>, PtCoO<sub>2</sub>, PdRhO<sub>2</sub> ■ Metallic carbides: Mo<sub>2</sub>C, AlVCrC, TiAl<sub>2</sub>Cr<sub>2</sub>C<sub>2</sub> ■ Intermetallic compounds: VPt<sub>2</sub>, MoNi<sub>3</sub>, NiIr<sub>2</sub> ■ Conductive borides: YCo<sub>2</sub>B<sub>6</sub>, NbFeB, Mn<sub>2</sub>B ■ Topological semimetals: CoSn, MoP, MoP<sub>2</sub>



**SUPREME**  
 SUPeRior Energy-efficient Materials and dEVICES

Materials Discovery and Processing  
 Accelerated Materials Discovery | AI-assisted Synthesis and Manufacturing | Processing and Metrology

## Roadmapping to ensure system-level impact

### Digital logic, control

- 0.3 fJ/switch

### Next gen analog & mixed signal

- > 10dB increase in SNR for same  $P_{DC}$
- $I_{on} = 5 \text{ mA}/\mu\text{m}$ ,  $SS=20 \text{ mV/decade}$
- RF amplifiers with 10x better performance

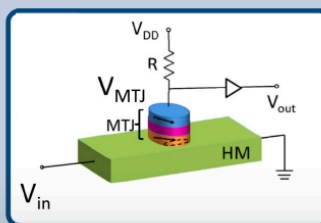
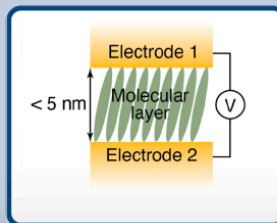
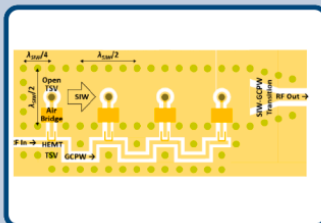
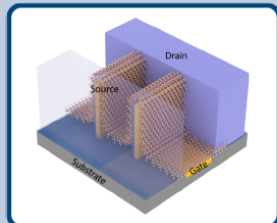
### High frequency, THz

- 1W at 300 GHz with 30% PAE

### Beyond CMOS

- < 5ns switching + 10000X < energy
- GHz spin torque oscillators
- $\Delta R > 500\Omega$  after magnet reversal

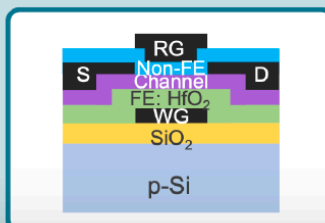
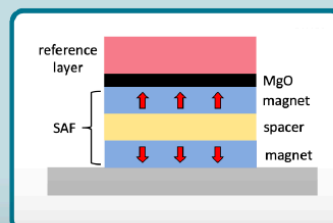
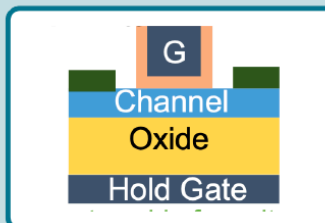
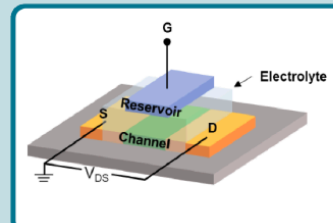
## Benchmarking against target device metrics



## Roadmapping to ensure system-level impact

Metric	2T-1MTJ	FeFET	2T eDRAM
Destructive Read?	No	No	No
Program voltage	< 0.5 V	1.8V	1V
Write energy	10-50 fJ	< 1 fJ	< 1 fJ
Write delay	< 1 ns	< 10 ns	1-10 ns
Read speed	< 1 ns	< 1 ns	< 1 ns
Endurance	> $10^{15}$	> $10^{12}$	> $10^{12}$

## Benchmarking against target device metrics



## Roadmapping to ensure system-level impact

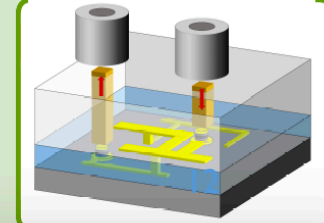
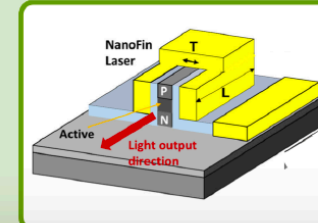
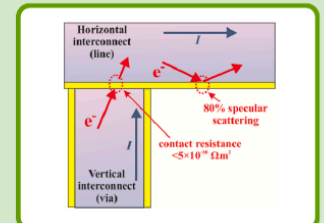
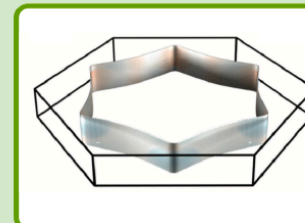
### Electrical interconnects

- >9X lower line resistance at 8 nm 1/2-pitch
- >80% specular surface scattering

### Inter-chip optical interconnects

- $\leq .01 \text{ I}^3$  laser size,  $\geq 160 \text{ GHz}$  direct mod speed
- $\leq 2 \text{ ps}$  laser turn on time

## Benchmarking against target device metrics



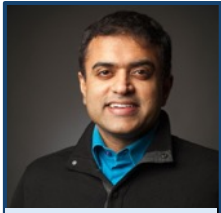
# Thrusts & PIs



Semiconductor  
Research  
Corporation

# Thrust 1: Digital and Analog

# Thrust 1: PIs and Projects



Debdeep Jena  
Thrust Lead



Tomas Palacios  
Co-Lead



H. Grace Xing



Eric Pop



James Hwang



Farnaz Niroui



Dan Ralph



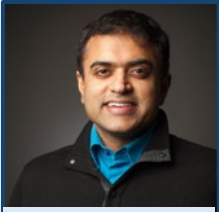
Luqiao Liu

**Project 1.1: Digital Logic and Control**

**Project 1.2: Next Generation Analog  
And Mixed Signal**

**Project 1.3: High Frequency  
and THz Devices**

# Thrust 1: PIs and Projects



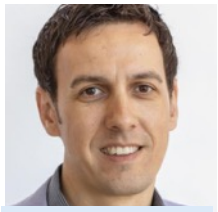
Debdeep Jena  
Thrust Lead



Tomas Palacios  
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H. Grace Xing



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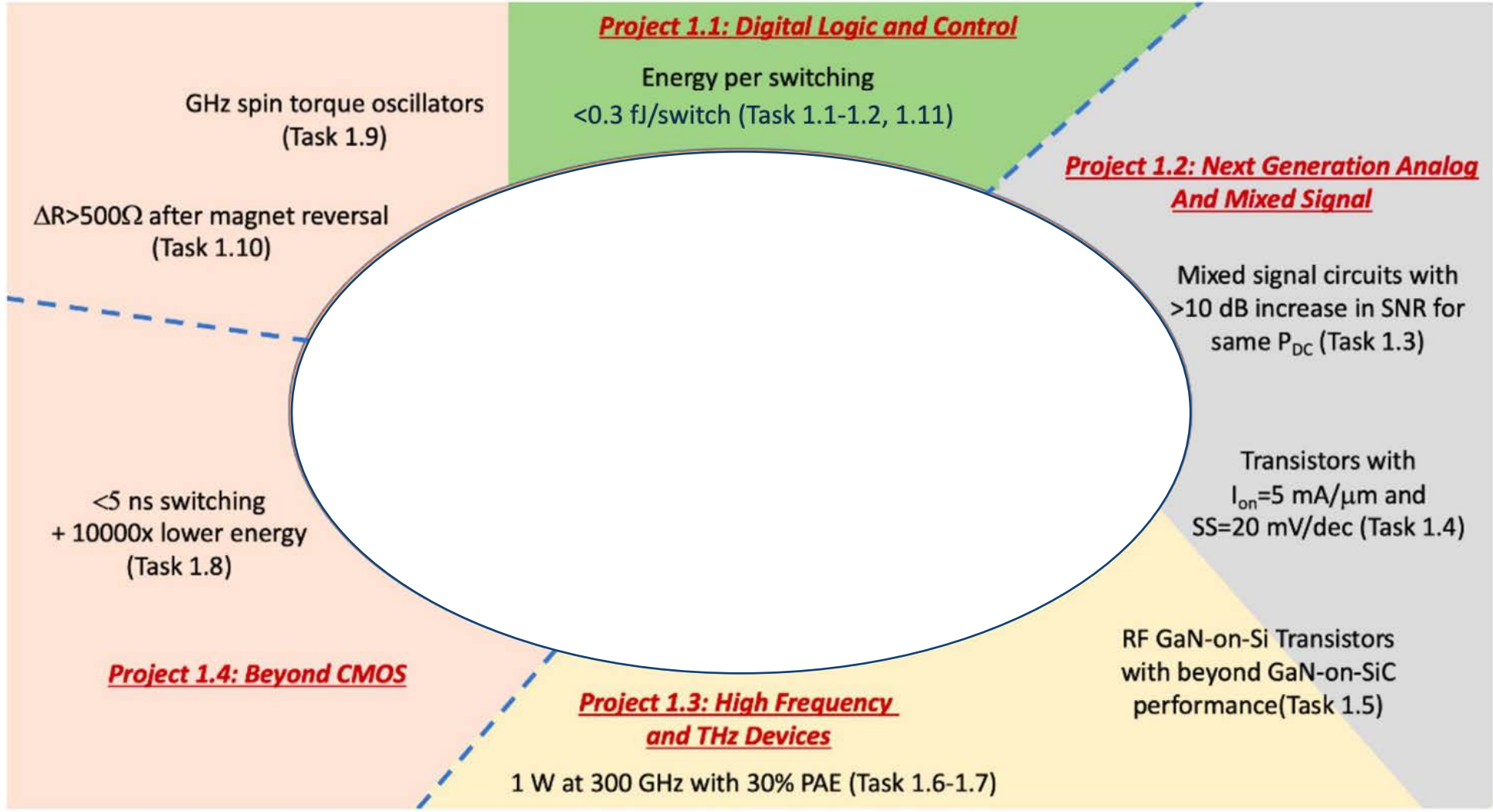
Farnaz Niroui



Dan Ralph

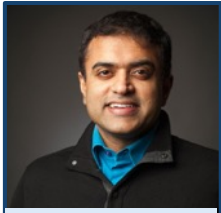


Luqiao Liu





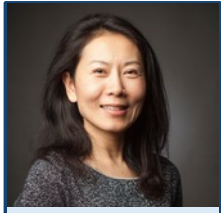
# Thrust 1: PIs and Projects



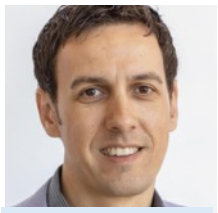
Debdeep Jena  
Thrust Lead



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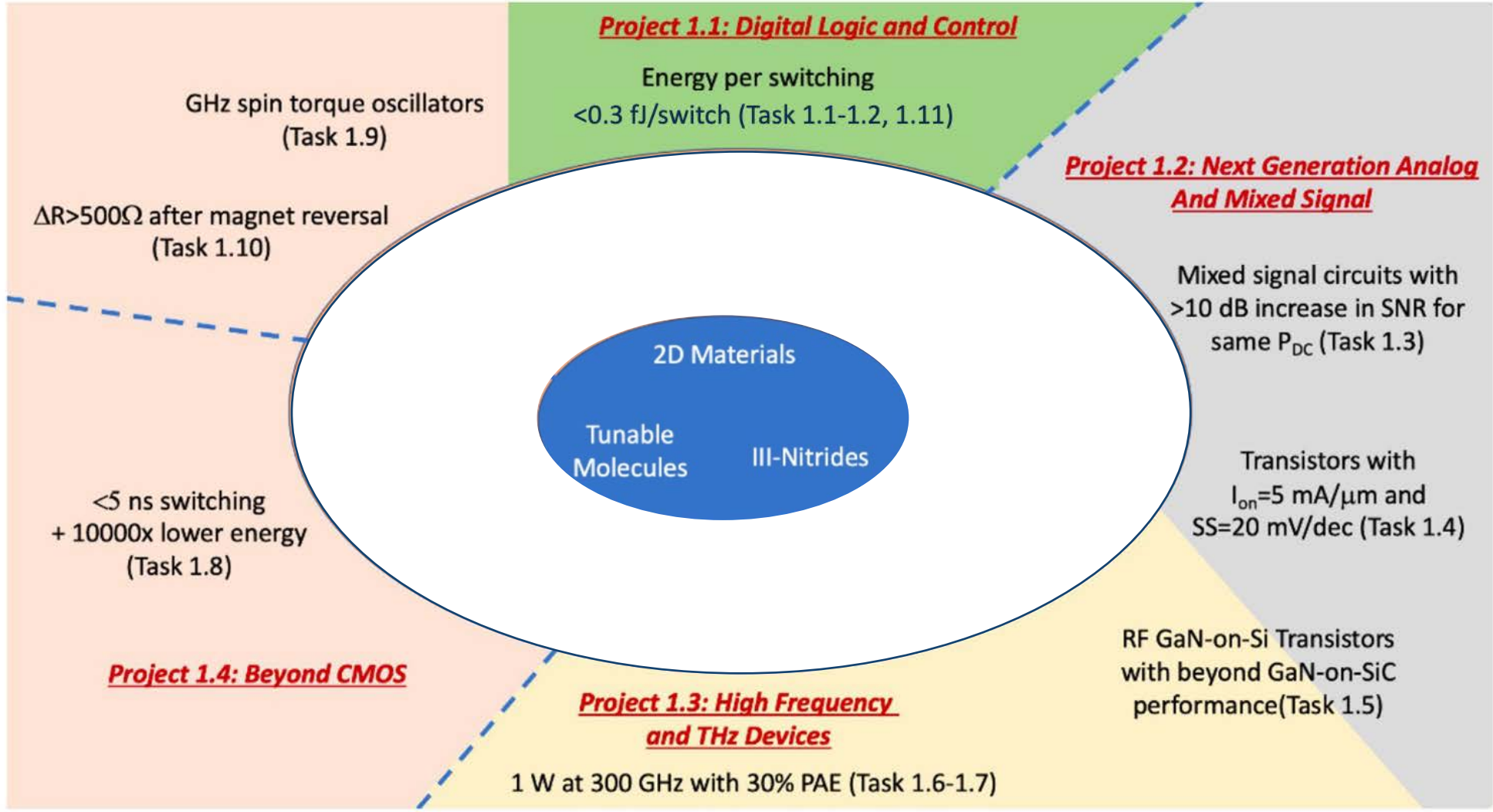
Farnaz Niroui



Dan Ralph



Luqiao Liu



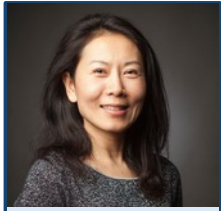
# Thrust 1: PIs and Projects



Debdeep Jena  
Thrust Lead



Tomas Palacios  
Co-Lead



H. Grace Xing



Eric Pop



James Hwang



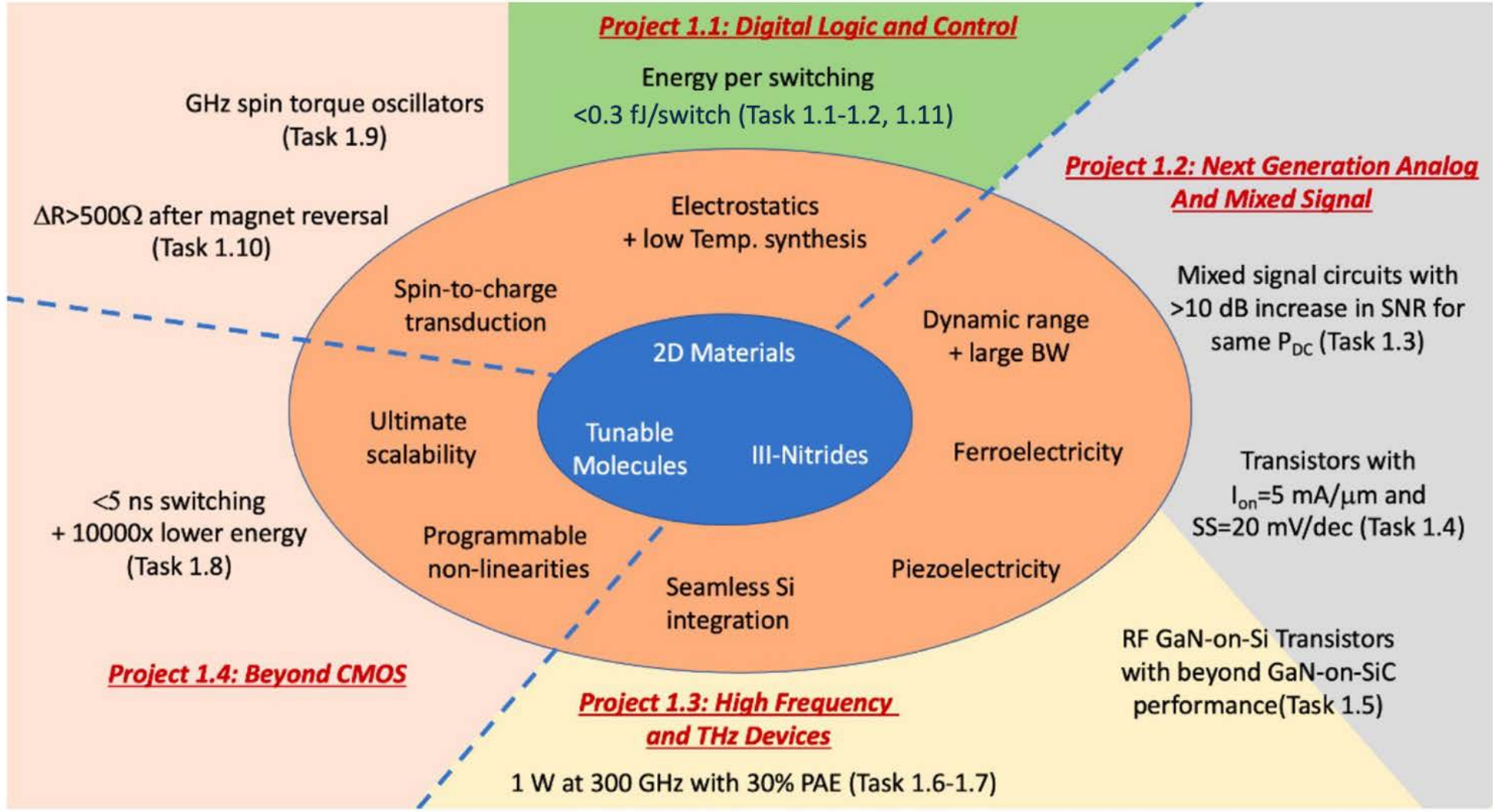
Farnaz Niroui



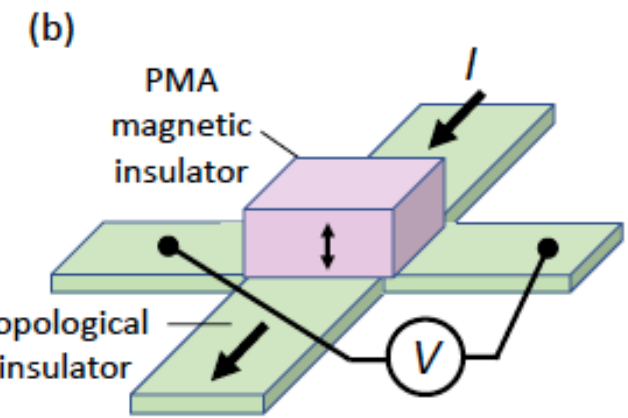
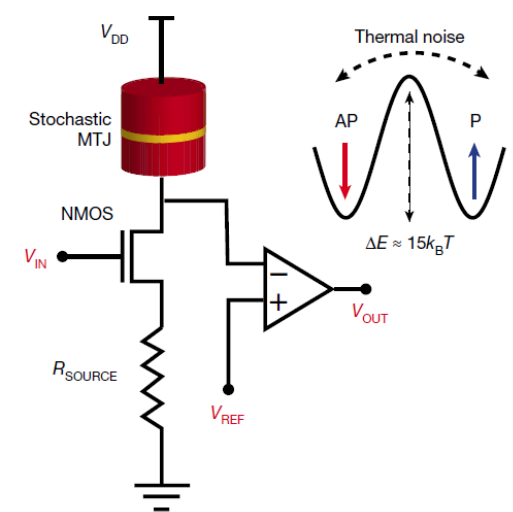
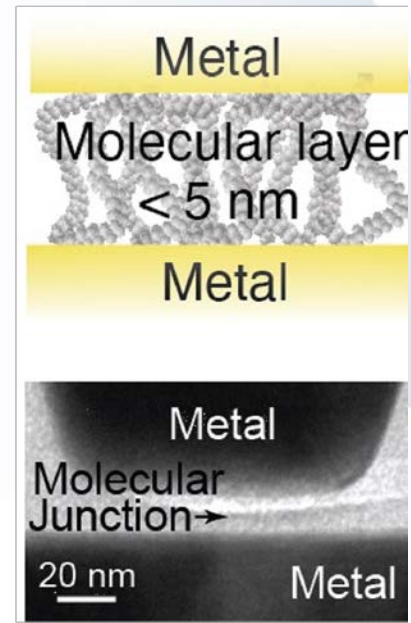
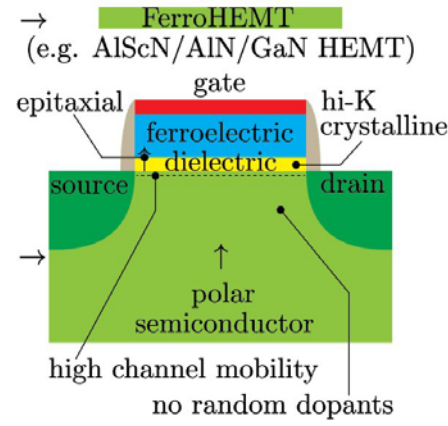
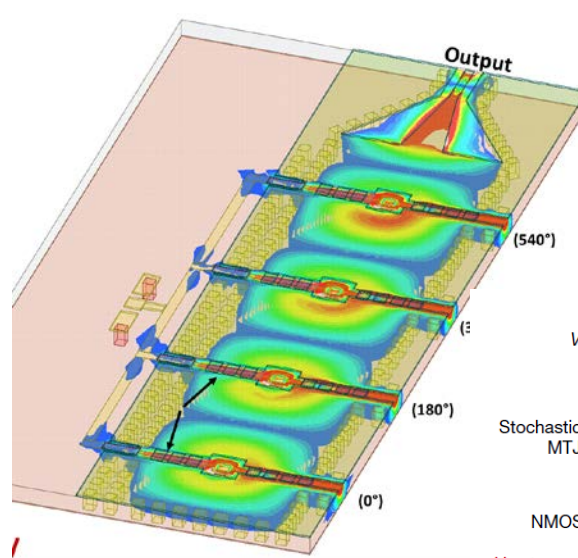
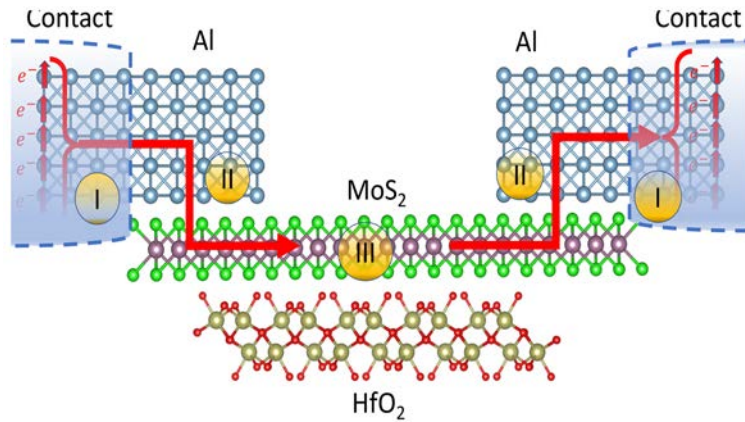
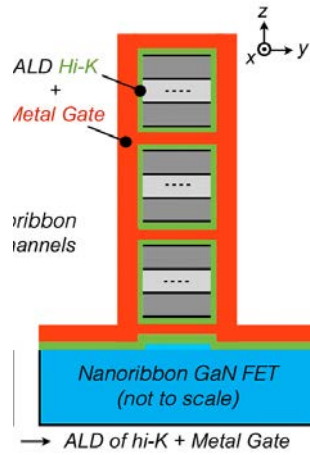
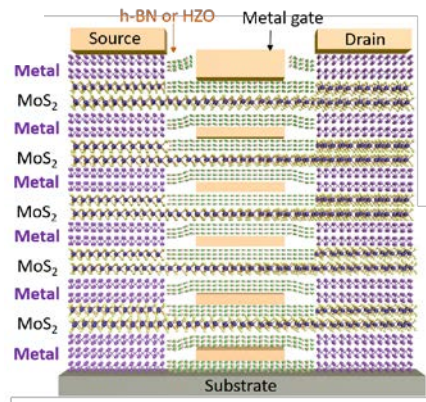
Dan Ralph



Luqiao Liu

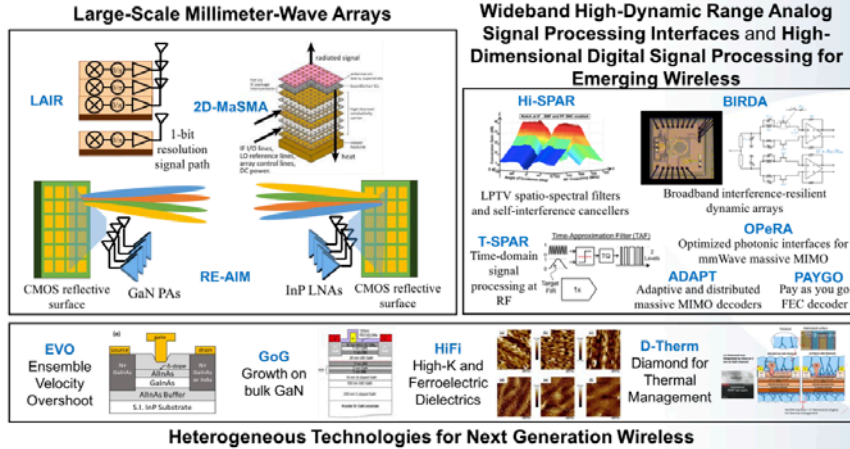


# Thrust 1

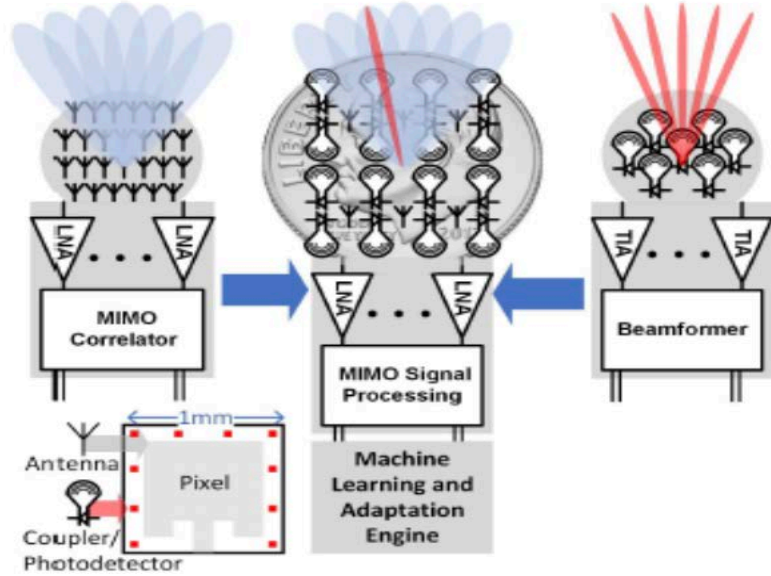


# Convergence with CUBIC, COGNISENSE, CHIMES

## Theme 3: Wireless Circuits and Technology



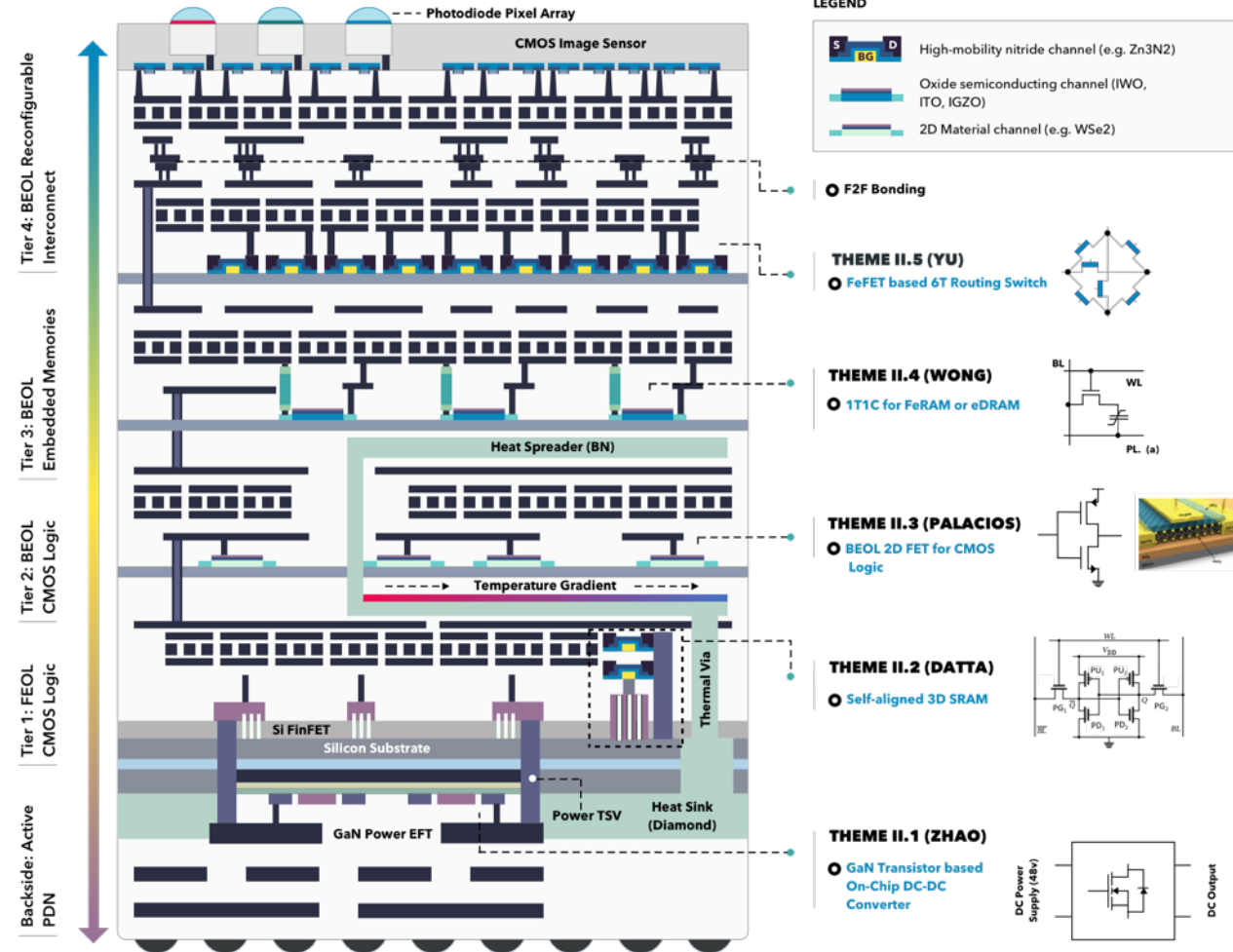
Heterogeneous Technologies for Next Generation Wireless



## CHIMES CENTER FOR HETEROGENEOUS INTEGRATION OF MICRO ELECTRONIC SYSTEMS

## Theme 3: Monolithic 3D (M3D) Densification and Diversification on Silicon Platform

MONOLITHIC 3D SEQUENTIAL INTEGRATION





Semiconductor  
Research  
Corporation

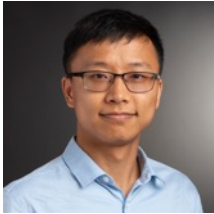
# Thrust 2: Memories and Applications

# Thrust-2 : Memories and Applications

Niemier



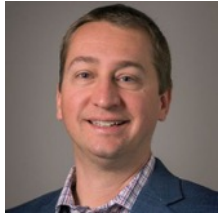
Ni



Khan



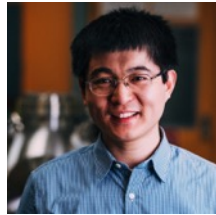
Hinkle



Ralph



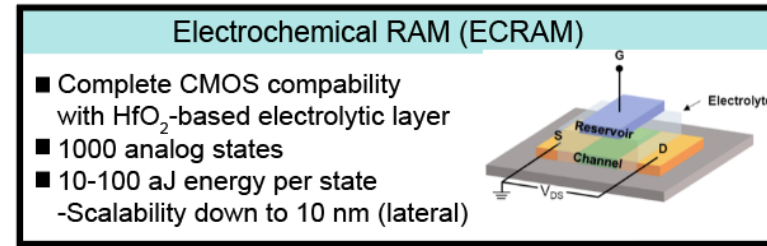
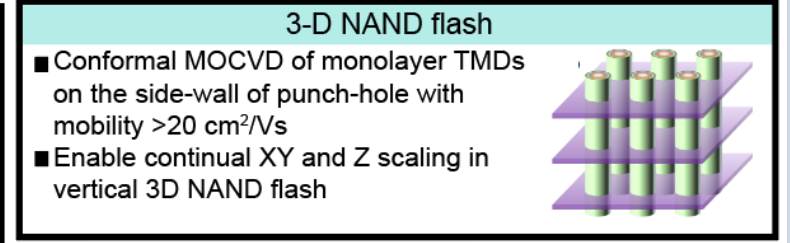
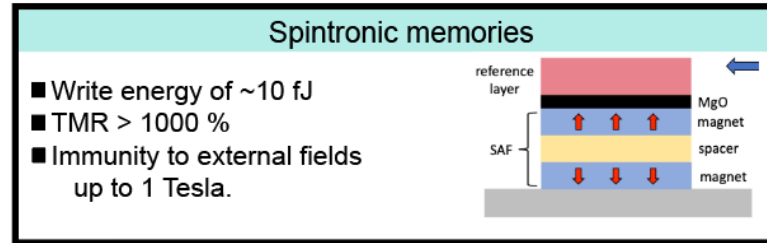
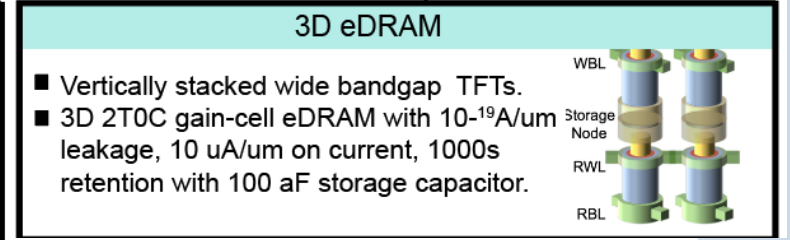
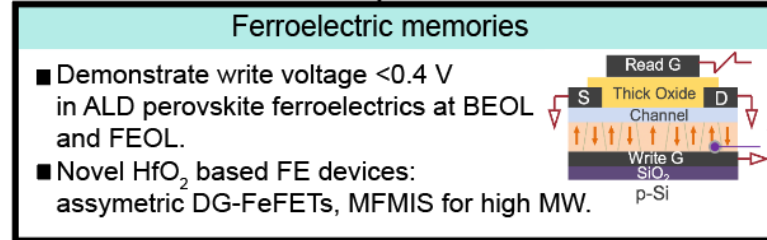
Lu



Rondinelli



Yildiz



**Thrust 4 - Materials Discovery & Processing**

Ferroelectrics $\text{HfO}_2$ , $\text{BaTiO}_3$ , $\text{SnS}$	TMDs $\text{MoSe}_2$ , $\text{WS}_2$ , $\text{WSe}_2$	Proton electrolyte in electrochemical RAM (ECRAM) - $\text{HfO}_2$ , $\text{ZrO}_2$	Synthetic antiferromagnets $\text{FeCoB/Pt/Ru/Pt/FeCoB}$	Proton channel in ECRAM - $\text{MoO}_3$
Non-cubic metals $\text{PtO}$ , $\text{Sr}_3\text{Ru}_2\text{O}_7$	Weyl semi-metals, Heusler alloys - $\text{Co}_2\text{MnGa}$ , $\text{Mn}_3\text{Sn}$	Proton reservoir in ECRAM - Metal hydrides, $\text{PdH}_x$	Insulator-metal transition materials for selectors $\text{La}_{0.5}\text{Sr}_{0.5}\text{CoO}_{0.3}$ , $\text{SrRuO}_3$ , $\text{LaCoO}_3$ , $\text{SrRuO}_3$	

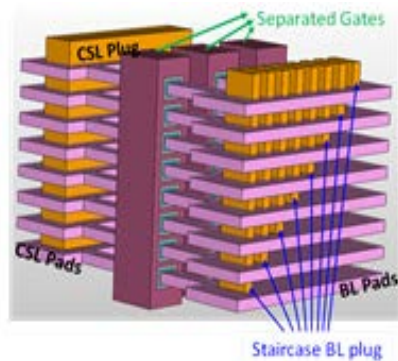
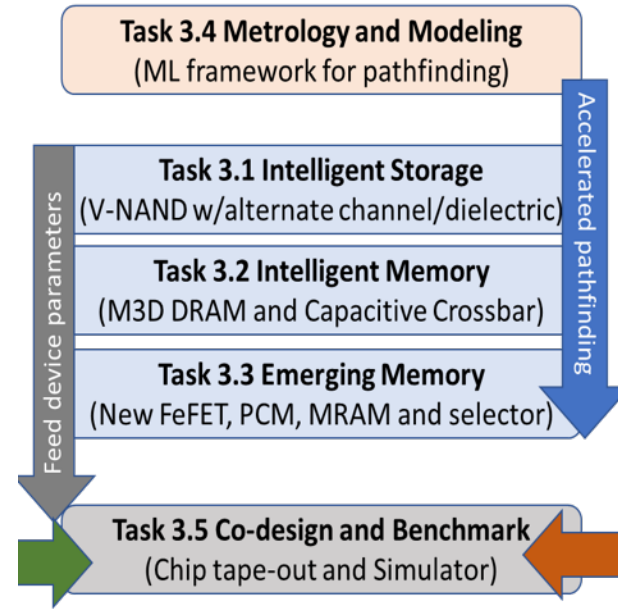


# Convergence with PRISM, CHIMES & COCOSYS



## Processing with Intelligent Storage and Memory

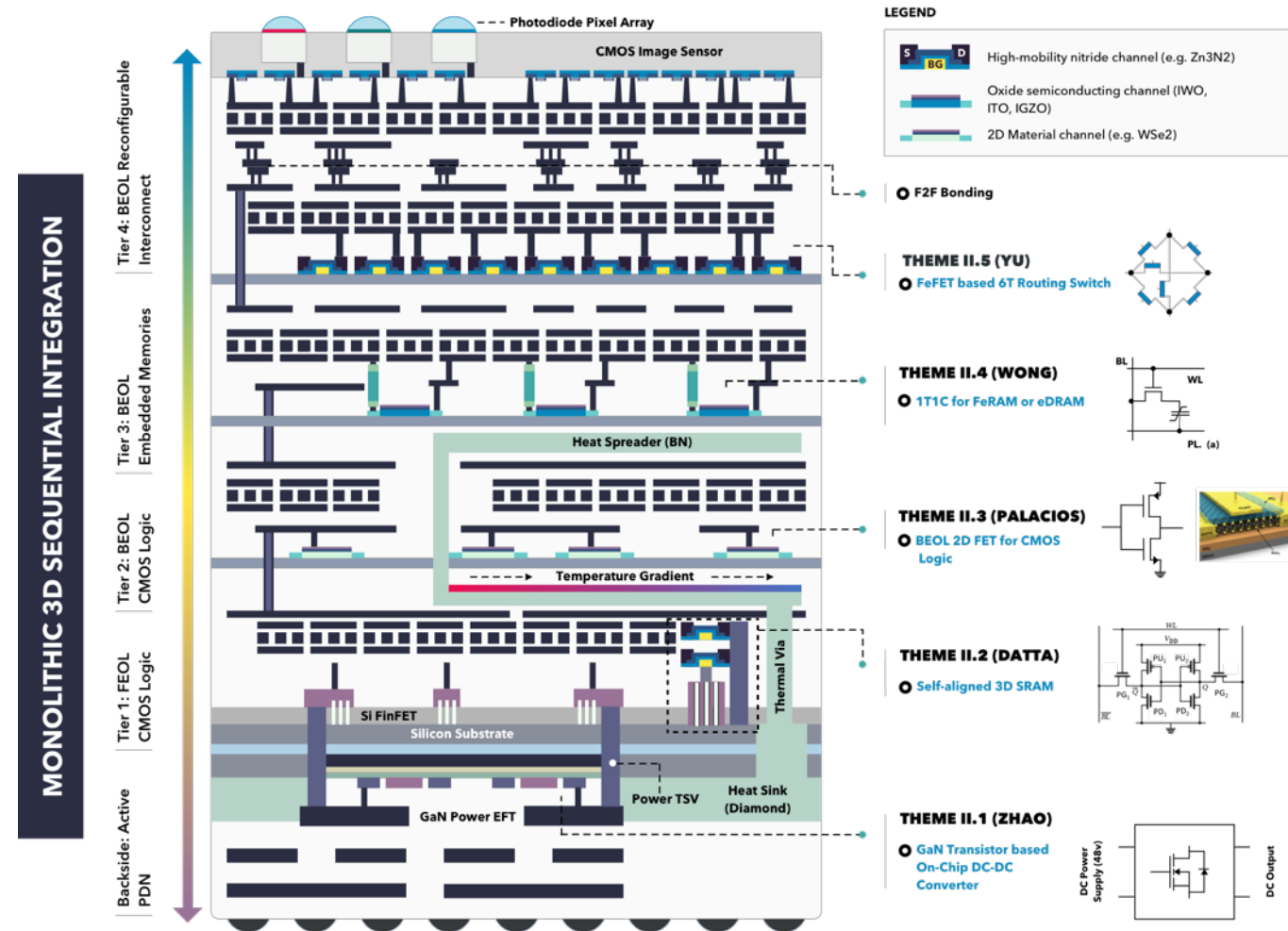
Theme 3: Devices and circuits



M3D DRAM

## CHIMES CENTER FOR HETEROGENEOUS INTEGRATION OF MICRO ELECTRONIC SYSTEMS

Theme 3: Monolithic 3D (M3D) Densification and Diversification on Silicon Platform







Semiconductor  
Research  
Corporation

# Thrust 3: Interconnects and Metrology



# Thrust 3

## Thrust 3: Interconnects and Metrology

- New materials: discovery and synthesis
- New processes and devices
- New high-throughput characterization schemes

### Project 3.1 Materials for Electrical Interconnects

- Anisotropic Fermi surface conductors
- Topological semimetals
- Engineering metal-metal and metal dielectric interfaces
- Accelerated materials discovery platforms
- Material synthesis



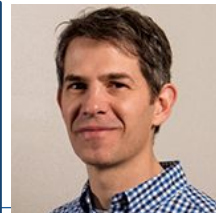
### Project 3.2 Materials and Devices for Optical Chip-to-Chip Interconnects

- Nanoscale semiconductor lasers, LEDs, and detectors
- Ultra-compact broadband optical modulators



### Project 3.3 Material Characterization and Metrology

- Nanoscale imaging: in-situ TEM studies
- Optical, terahertz, spin resonance characterization
- High-throughput electronic characterization
- Thermal engineering, modeling and characterization
- Surface and interface characterization



### Project 3.4 Interconnect Benchmarking

- Benchmark new interconnect ideas with respect to system level performance benefits



# Task 3.1 Materials discovery and benchmarking for interconnects $\leq 8$ nm

## • Objective

- Materials discovery/benchmarking
- Demonstrate interconnect solution which outperforms Ru, Cu, Co

## • PI/Collaborators:

- Daniel Gall (lead); Tang, Cha, Rana

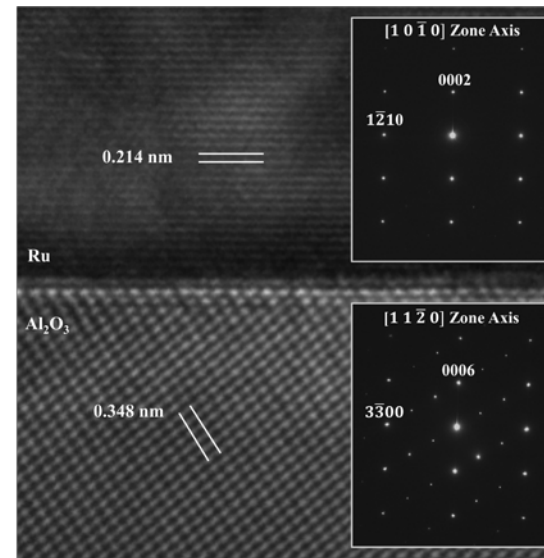
## • Innovative claims

- *In situ* measurements of intrinsic resistivity scaling
- Directional conductors
- Synthesize theoretically predicted conductors

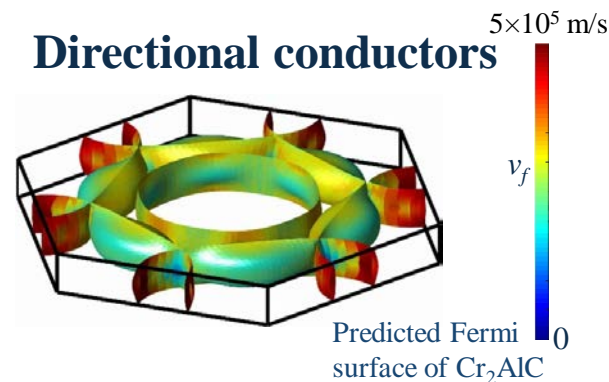
## • Year 3 accomplishment goals

- Quantify resistivity scaling in boride, oxide, and directional conductors.
- Blanket layer stack with  $>1.5 \times 10^{15} \Omega^{-1} \text{m}^{-2}$ .

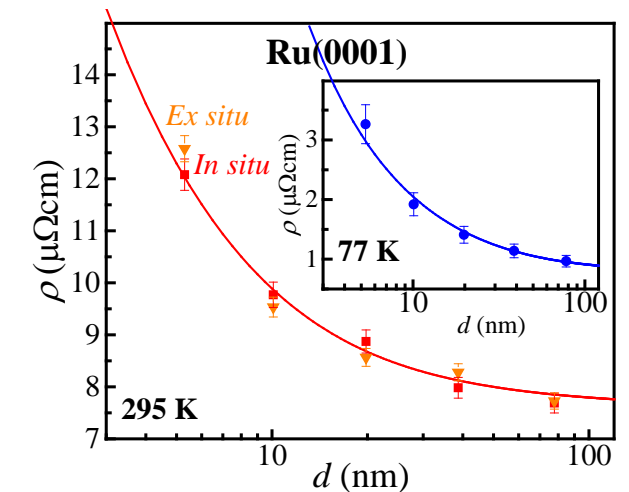
## Epitaxial Layers



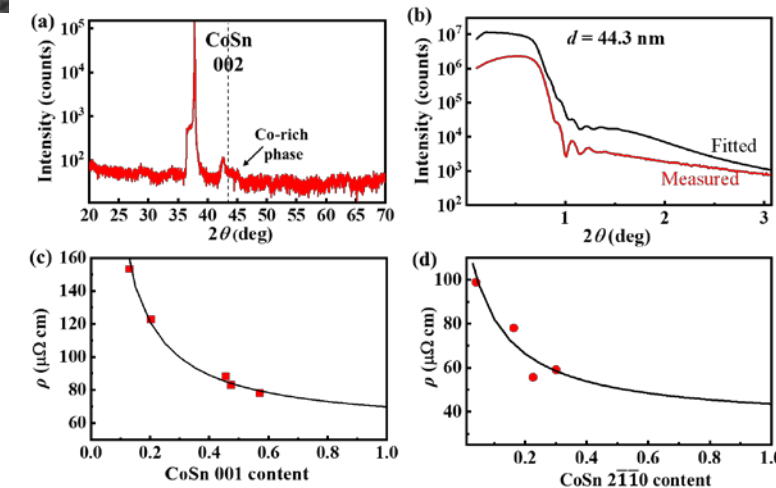
## Directional conductors



## *In situ* Transport



## Explore new materials (e.g. CoSn)



# Task 3.4: Materials and Designs for Nanoscale Light Sources

- Objective

- Materials and designs for nanoscale semiconductor lasers and LEDs for chip-to-chip optical interconnects

- PI/Collaborators:

- Farhan Rana (lead); Jing Kong, Hong Tang, Mike Niemier, Xing/Jena, CHIMES PIs

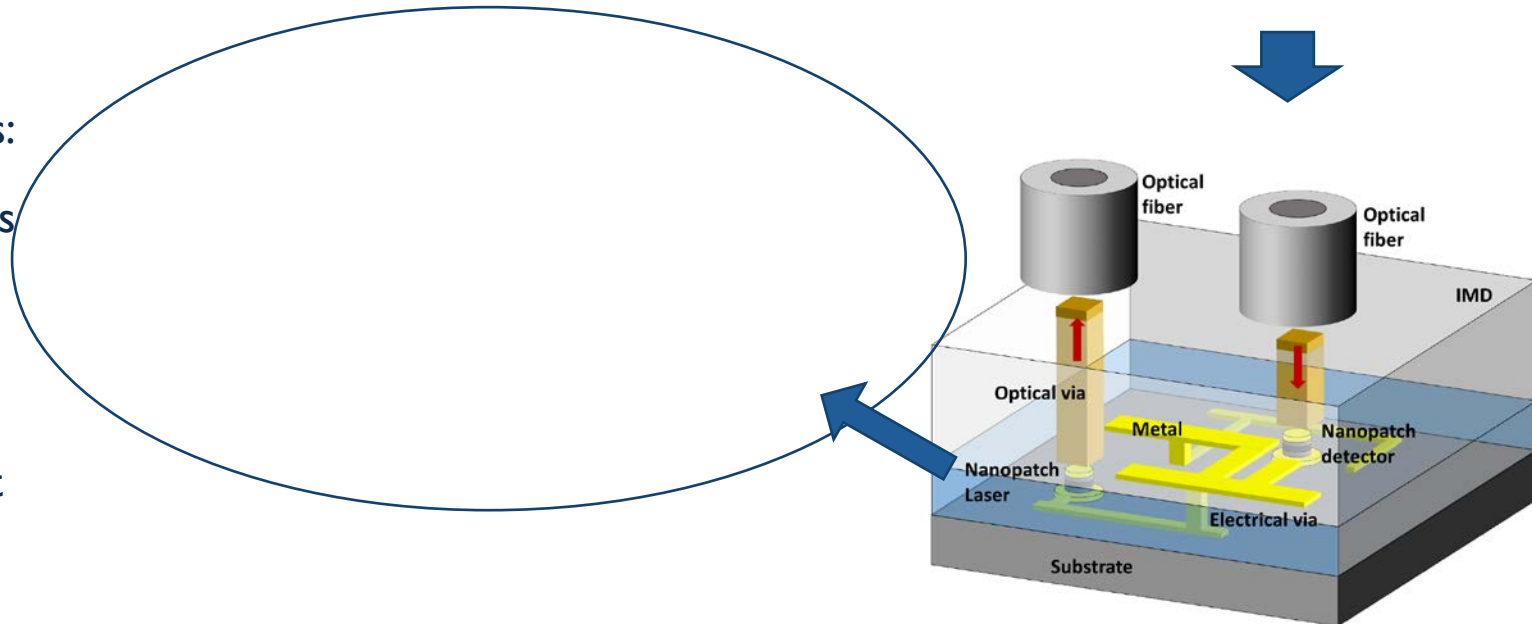
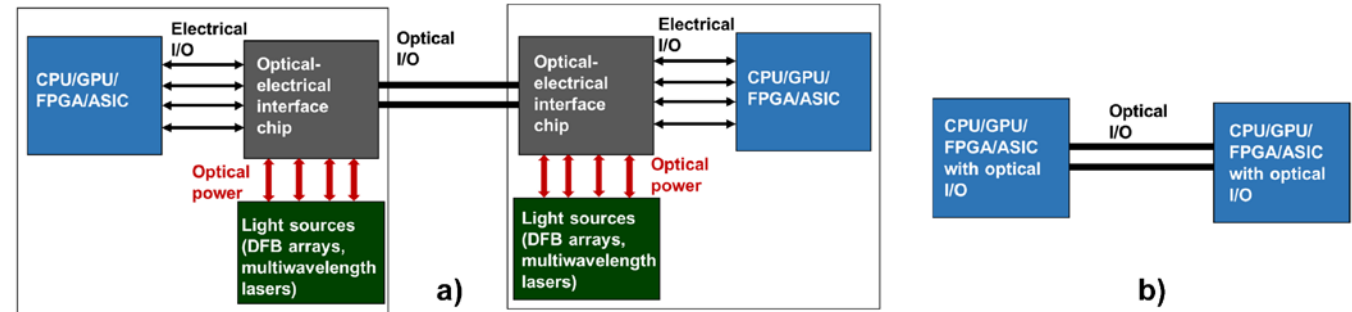
- Innovative claims

- Use new materials for BEOL integration: e.g. 2D materials
- Use new materials for lower optical losses: e.g. transition metal nitrides
- Benchmark system level performance gains

- Year 3 accomplishment goals

- Direct current modulation with CMOS electronics
- > 80 Gb/s data rates, < 5 fJ/bit EO transduction, & < 0.1 sq-microns footprint
- Highly directional output

State of the art (not compact and power hungry) → new designs



# Task 3.10 Accelerated Materials Platform and Interconnects

## • Objective

- Develop high-throughput materials synthesis and characterization techniques
- Make new interconnects that can outperform Cu and Ru at scaled dimensions

## • PI/Collaborators:

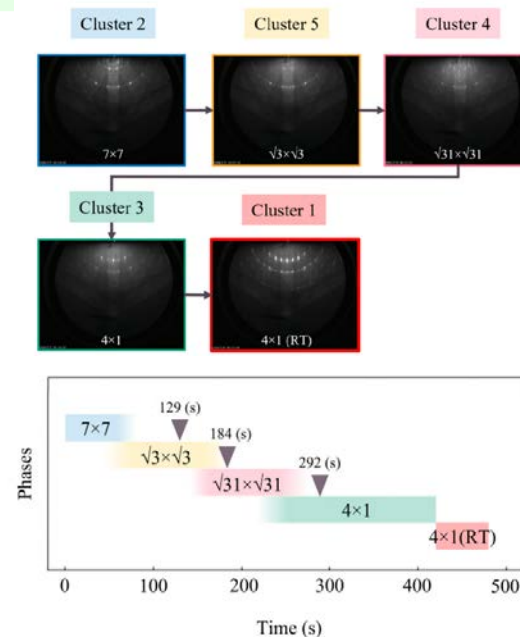
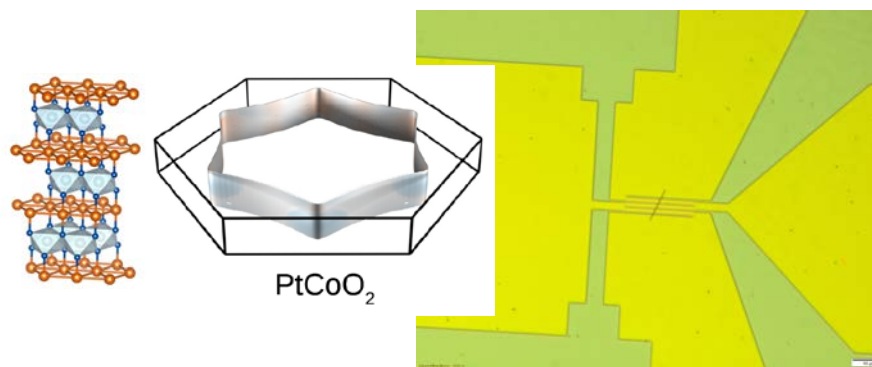
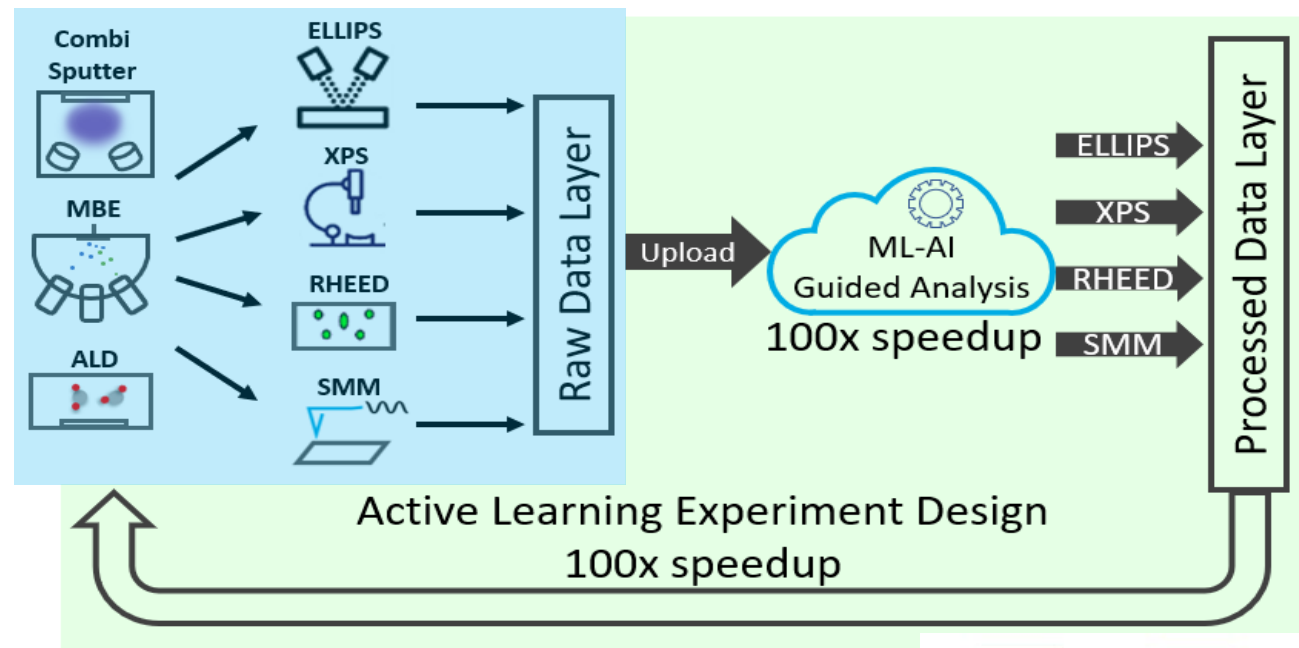
- Chris Hinkle (lead); Rondinelli, Gall, Cha, Pop

## • Innovative claims

- 10-100x speedup in materials synthesis/characterization
- Active learning experiments with ML-guided materials characterization
- New interconnects predicted by high-throughput and de novo theory

## • Year 3 accomplishment goals

- ML-guided diffraction, XPS, ellipsometry, scanning microwave impedance microscopy
- Interconnect materials with lower resistivity than Cu and Ru at  $< 200 \text{ nm}^2$  conductor area



# Task 3.11: Thermal Engineering & Materials for 3D Integration

- Objective

- Electro-thermal co-design of materials, devices, interconnects

- PI/Collaborators:

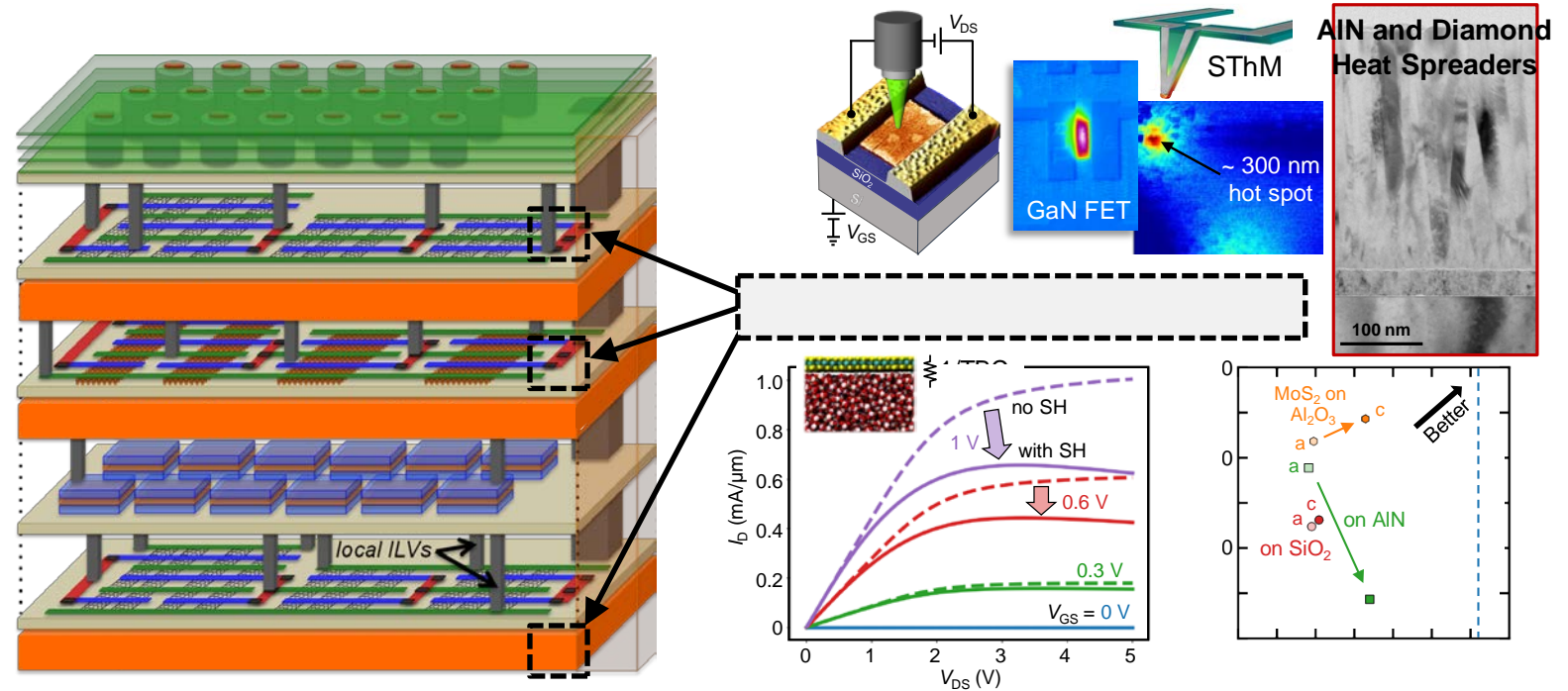
- Eric Pop (lead); Hinkle (mater.), Giustino (model), Xing, Gall, Cha, Theme 6 Center

- Innovative Claims:

- Thermal modeling of 2D and RF transistors + topological interc.
- Unique thermal measurement capability (Raman, SThM)

- Year 3 Accomplishment Goals:

- Electro-thermal model of 2D and RF transistors, including finite-element and (approximate) analytic models
- Clear guidelines for optimization of heat spreading, e.g. material property vs. thermal boundary resistance

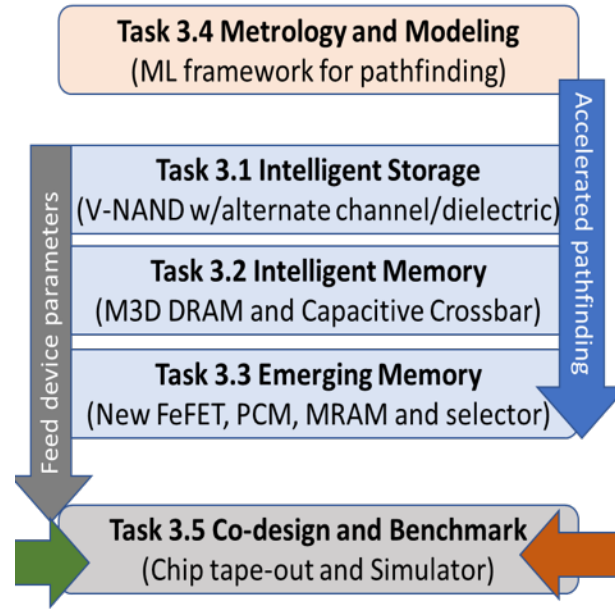


# Convergence with PRISM & CHIMES

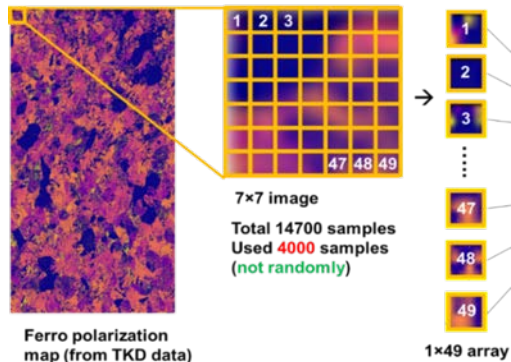


## Processing with Intelligent Storage and Memory

Theme 3: Devices and circuits

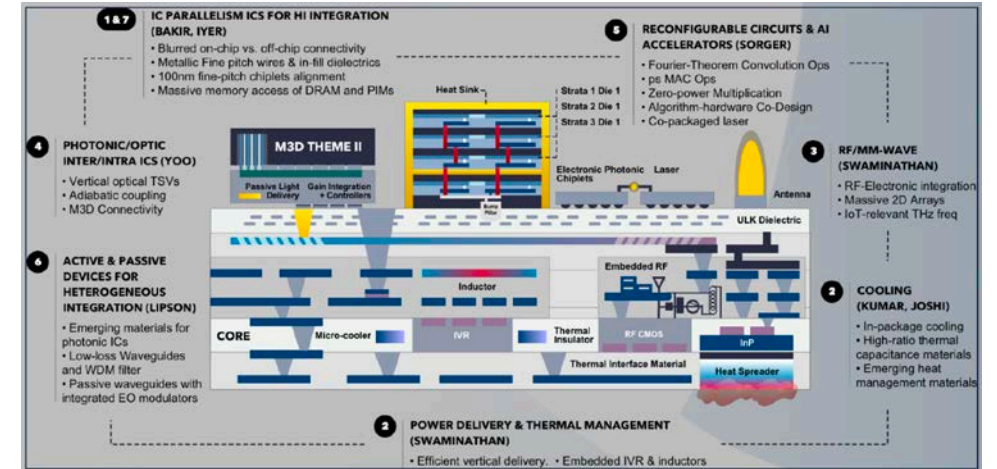


## Metrology

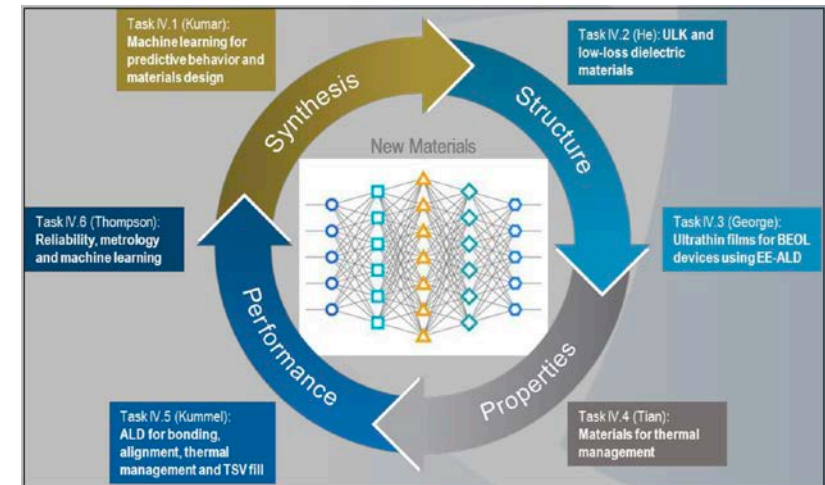


## CHIMES CENTER FOR HETEROGENEOUS INTEGRATION OF MICRO ELECTRONIC SYSTEMS

Theme III: Ultra-dense Heterogeneous Interconnect & Assembly



Theme IV: Materials Behavior, Synthesis, Metrology & Reliability





Semiconductor  
Research  
Corporation

# Thrust 4: Materials Discovery and Processing





# Thrust 4 Investigators and relation to Center



**Center 7: SUPeRior Energy-efficient Materials and dEVICES (SUPREME)**

**Thrust 1:**  
Digital & Analog

**Thrust 2:**  
Memories & Applications

**Thrust 3:**  
Interconnects

**Thrust 4: Materials Discovery & Processing**

Lead	Feliciano Giustino	UT Austin	Co-Lead	Jing Kong	MIT
	Chris Van deWalle	UCSB		Steven George	UC Boulder
	James Rondinelli	Northwestern		Elton Graugnard	Boise State
	Debdeep Jena	Cornell		Darrell Schlom	Cornell
	Bilge Yildiz	MIT		Greg Parsons	NCSU

(Theorists)

(Experimentalists)

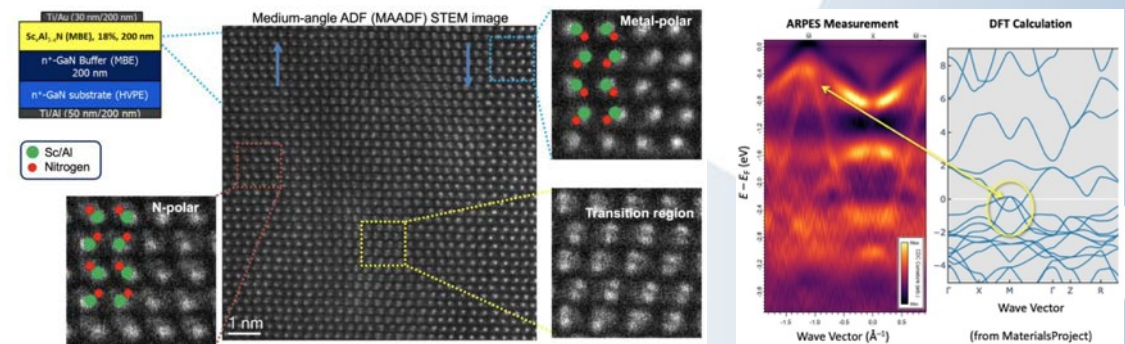
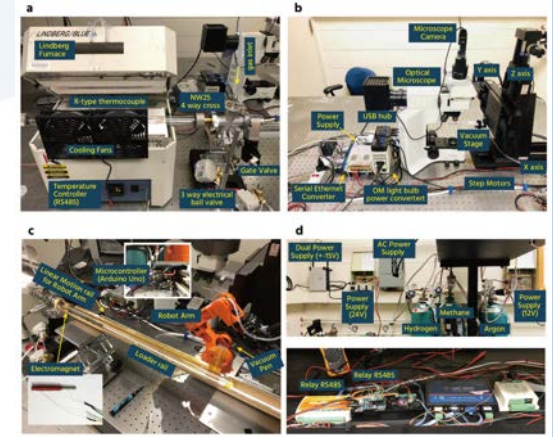
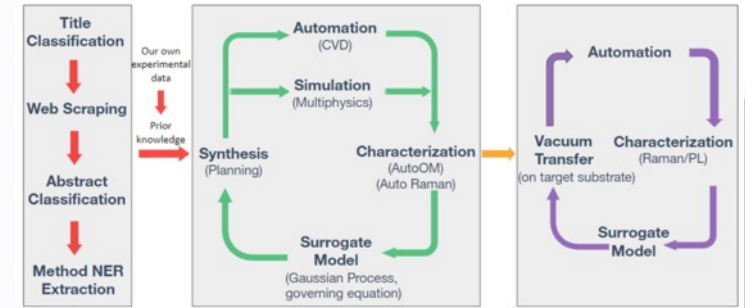
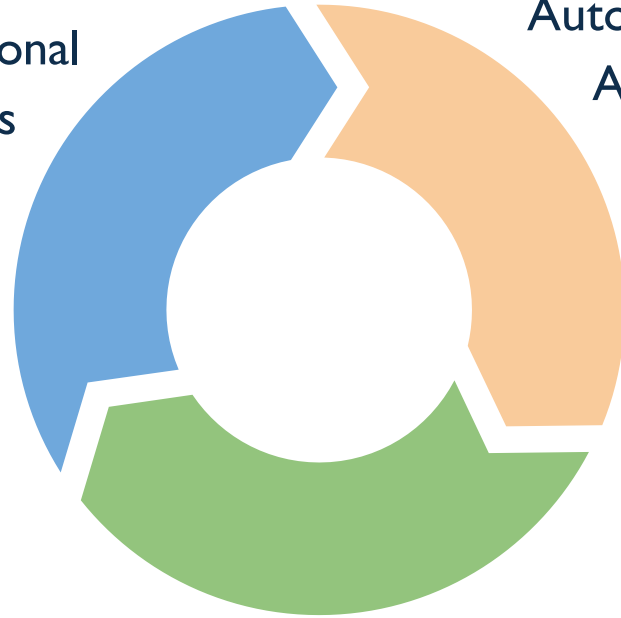
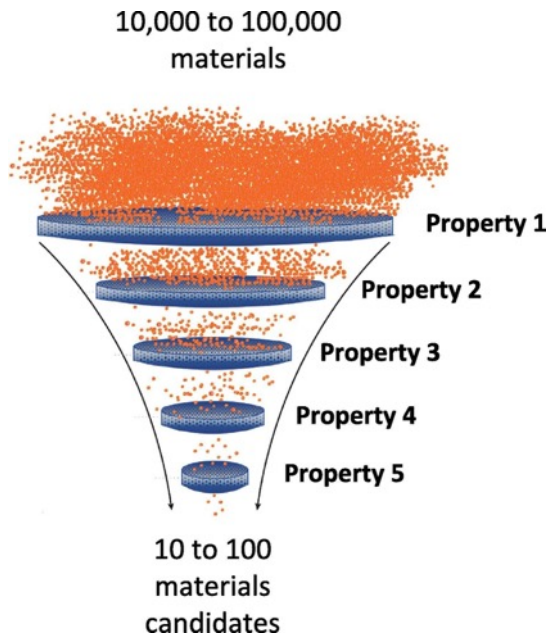
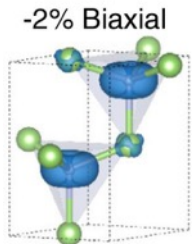
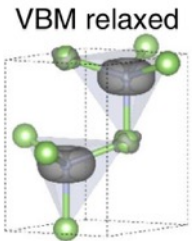
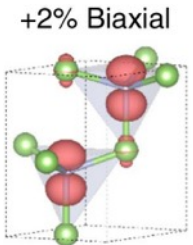
# Thrust 4 Vision & Mission

## Materials Discovery & Advanced Processing

Computational  
Materials  
Discovery

Autonomous  
AI-driven  
Synthesis

Characterization &  
Processing



# Thrust 4 Vision & Mission

## Materials Discovery

### Leads



Team meetings  
TBD

Workshop (TBD)

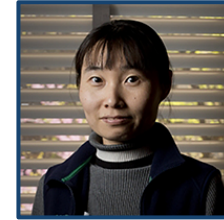


### High throughput



## Advanced Processing

### Leads

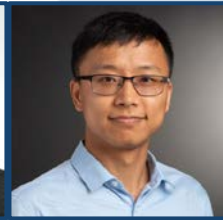


Team meetings  
Every Monday at 3:30pm ET

Workshop (TBD)



### In the context of devices



# Thrust 4 Topics

13 tasks focusing on 4 classes of materials

**2D Materials** (e.g. TMDs and more)

**Large Gap Channel Materials** (e.g. GaN, oxides)

**New Ferroelectrics, high-K and Nonlinear Materials** (e.g. AlScN, perovskite oxides)

**Ionic materials for Electrochemical RAMs** (oxides, oxynitrides, etc)

# Thrust 4 Tasks

2D Materials	Ferroelectric & nonlinear materials
Large gap channel materials	Ionic synapses

Task 4.1	High-throughput discovery of high-mobility 2D channel materials	Giustino
Task 4.2	High-quality 2D materials discovery and growth via BEOL compatible approaches	Kong
Task 4.3	Artificial Intelligence-Assisted Synthesis and Integration Optimization of 2D Materials (eg G/BN)	Kong
Task 4.4	Controlled Etching of 2DTMD Films Using Electron-Enhanced Atomic Layer Etching with Reactive Background Gas	George
Task 4.5	Discovery of high mobility p-type nitride semiconductors for wide bandgap CMOS (eg GaN)	Jena
Task 4.6	n-type and p-type oxide channel materials for complementary transistor technology (eg PdO)	Schlom
Task 4.7	AlScN and related alloys as nonlinear optical and piezoelectric materials	Van deWalle
Task 4.8	New ferroelectric and High-K materials (theory, epitaxy, and ALD)	Jena
Task 4.9	Discovery of channel materials with the highest sensitivity of electronic conductivity to proton insertion	Yildiz
Task 4.10	BEOL Area-Selective Atomic Layer Deposition of Conformal Crystalline 2D Materials (eg TMDs)	Graugnard
Task 4.11	Atomic Layer Deposition of Ultrahigh-k Dielectrics (eg BaHfO <sub>3</sub> )	Graugnard
Task 4.12	Inherent Selective Atomic Scale Processing	Parsons
Task 4.13	Active and Physics-Informed Machine Learning for Accelerated Materials Discovery (eg ME/FE oxides)	Rondinelli

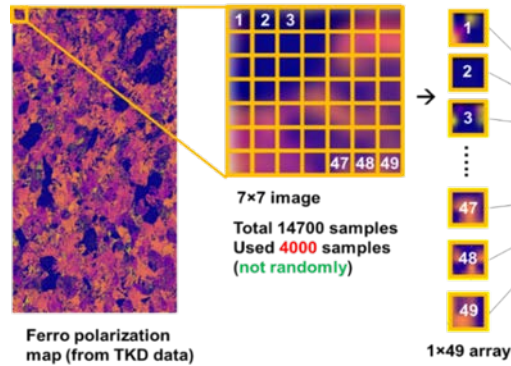
# Convergence with PRISM & CHIMES



## Processing with Intelligent Storage and Memory

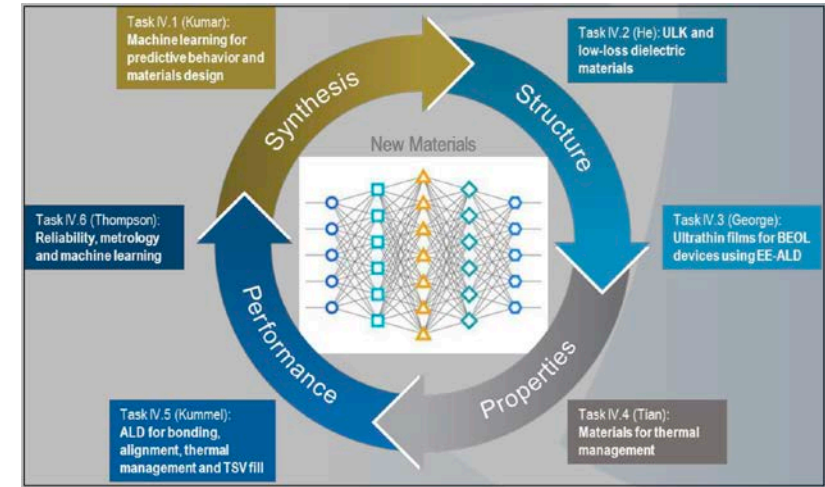
Theme 3: Devices and circuits

Metrology



## CHIMES CENTER FOR HETEROGENEOUS INTEGRATION OF MICRO ELECTRONIC SYSTEMS

Theme IV: Materials Behavior, Synthesis, Metrology & Reliability

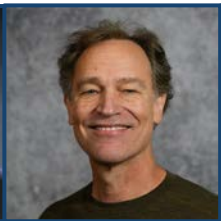
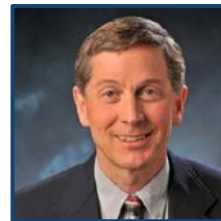


## Advanced Processing – a Inter-Center Topic

Elton Graugnard



SUPREME PIs



& PRISM PIs & CHIMES PIs

Workshop (TBD)

# Organization Chart: SUPREME Thrust-Liaison Meetings on every Wednesday@4pm ET (sign up for SUPREME task)

**Center 7: SUPeRior Energy-efficient Materials and dEVICES (SUPREME)**

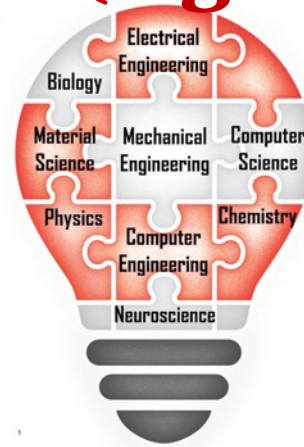


**H. Grace Xing<sup>v</sup>**  
Director

**Tomas Palacios**  
Associate Director

**Thomas Dienel**  
Managing Director

**FUNCTIONS**  
Project, Budget & Conflict Management, Strategic Planning, Annual Meeting Coordination, IP/Spin-off Coordination, Research Development, Reporting




**Scientific Advisory Board**  
Visionaries funding a shared technology future



**FUNCTIONS**  
Center Evaluation, Strategic Planning and PI Re-alignment, IP Filing Decision, Center to Center Collaboration


**Thrust 1: Digital & Analog**



**Debdeep Jena Thrust Lead**

- Tomas Palacios (Co-Lead)
- H. Grace Xing
- James Hwang<sup>1</sup>
- Farnaz Niroui<sup>^1v</sup>
- Luqiao Liu<sup>\*^</sup>

**Thrust 2: Memories & Applications**



**Asif Khan<sup>^</sup> Thrust Lead**

- Dan Ralph (Co-Lead)
- Kai Ni<sup>^</sup>
- Mike Niemier\* (Liaison Lead)
- Bilge Yildiz<sup>1v</sup>

**Thrust 3: Interconnects & Metrology**



**Farhan Rana Thrust Lead**

- Daniel Gall (Co-Lead)
- Hong Tang<sup>1</sup>
- Judy Cha<sup>\*^v</sup>
- Chris Hinkle
- Eric Pop

**Thrust 4: Materials Discovery & Processing**



**Feliciano Giustino<sup>o</sup>**  
Thrust Lead

- Jing Kong<sup>1v</sup> (Co-Lead)
- Steven George
- Chris Van de Walle
- Darrell Schlom<sup>\*</sup>
- James Rondinelli
- Elton Graugnard
- Greg Parsons

<sup>\*</sup> Liaisons to interface with other JUMP 2.0 centers  
<sup>1</sup> First-time SRC Performers (6)  
<sup>^</sup> Young Faculty (5)  
<sup>v</sup> Female Faculty (5)

**Note: Only primary thrust affiliation is shown.**

# Q&As

